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- (71) Applicant (*for all designated States except US*): CAM-
BRIOS TECHNOLOGIES CORPORATION [US/US];

930 East Arques Avenue, Sunnyvale, California 94085 (US).

- (72) Inventors; and
(75) Inventors/Applicants (*for US only*): BHATIA, Rimple [US/US]; 861 Covington Road, Los Altos, California 94024 (US). PAKBAZ, Hash [US/US]; 2466 Carisbrook Court, Hayward, California 94542 (US). SEPA, Jelena [RS/US]; 974 Leighton Way, Sunnyvale, California 94087 (US). RAMOS, Teresa [US/US]; 417 Atlanta Avenue, San Jose, California 95125 (US). PSCHENTZKA, Florian [DE/US]; 628 A Church Street, San Francisco, California 94114 (US). SPAID, Michael, A. [US/US]; 780 Shary Avenue, Mountain View, California 94041 (US). PICHLER, Karl [AT/AT]; Hall 530-4, 8911 Admont (AT).

[Continued on next page]

- (54) Title: NANOSTRUCTURE-BASED TRANSPARENT CONDUCTORS HAVING INCREASED HAZE AND DEVICES COMPRISING THE SAME

FIG. 2A

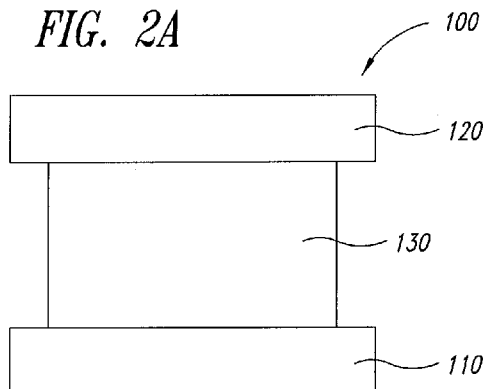
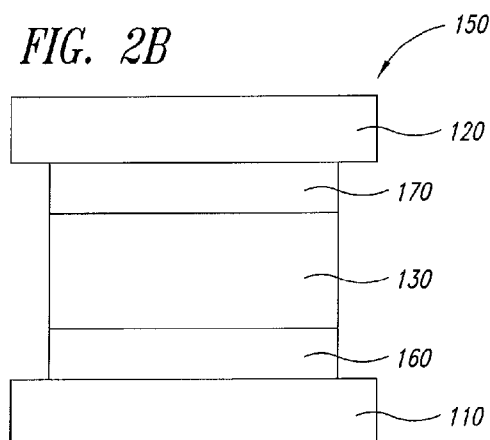


FIG. 2B



- (57) Abstract: The present disclosure relates to modifications to nanostructure based transparent conductors to achieve increased haze/light-scattering with different and tunable degrees of scattering, different materials, and different microstructures and nanostructures.



(74) **Agents:** HAN, Hai et al.; Seed Intellectual Property Law Group PLLC, Suite 5400, 701 Fifth Avenue, Seattle, Washington 98104-7064 (US).

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